

Supporting Information
A combined XPS and computational study of the
chemical reduction of BMP-TFSI by lithium

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Table S1: Remaining relative intensities of the different XP peaks related to a multilayer BMP-TFSI film during post-deposition of increasing amounts of Li at room temperature.

	C_{BMP}	N_{BMP}	C_{TFSI}	N_{TFSI}	F_{TFSI}	O_{TFSI}	S_{TFSI}
BMP-TFSI	100%	100%	100%	100%	100%	100%	100%
0.4 MLE Li	n.a.	100%	n.a.	91%	n.a.	n.a.	n.a.
0.7 MLE Li	n.a.	95%	n.a.	60%	n.a.	n.a.	n.a.
1.4 MLE Li	98%	84%	48%	34%	71%	61%	53%
2.2 MLE Li	83%	57%	36%	23%	54%	66%	37%
3.1 MLE Li	n.a.	30%	n.a.	9%	n.a.	n.a.	n.a.
3.6 MLE Li	51%	13%	31%	0%	44%	60%	24%